

PATENT

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
PATENT EXAMINING OPERATION**

Applicant(s): Philippe Staib

Serial No:

Group Art Unit:

Filed: September 17, 2003

Examiner:

Att. Docket No.: B1180/20019

Confirmation No.:

For: ELECTRON DIFFRACTION SYSTEM FOR USE IN PRODUCTION
ENVIRONMENT AND FOR HIGH PRESSURE DEPOSITION TECHNIQUES

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom. No representation is made that the reference(s) is/are prior art with respect to this application.

This Information Disclosure Statement is being filed within three months of the filing date of a national application other than a CPA under 37 CFR § 1.53(d), within three months of the date of entry of the national stage as set forth in 37 CFR § 1.491 in an international application, before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of an RCE under 37 CFR § 1.114. No certification or fee is required. 37 CFR § 1.97(b).

Attorney Docket No. B1180/20019
IDS dated September 17, 2003

The reference(s) was/were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.

Respectfully submitted,

CAESAR, RIVISE, BERNSTEIN,
COHEN & POKOTILOW, LTD.


September 17, 2003

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By



David M. Tener
Registration No. 37,054
Customer No. 03000
(215) 567-2010
Attorneys for Applicant(s)

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Substitute for PTO/SB/08A (08-00)
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Substitute for Form 1449A/PTO INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheet as necessary)				Complete if Known Application Number Filing Date First Named Inventor Group Art Unit Examiner Name Attorney Docket Number			
Sheet 1 of 1				September 17, 2003 Philippe Staib B1180/20019			

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No.	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY
		Number	Kind Code (if known)		
		3,777,211		KUIJPERS	12-04-1973

FOREIGN PATENT DOCUMENTS							
Examiner Initials*	Cite No.	Foreign Patent Document			Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	T
		Office	Number	Kind Code (If known)			
		EP	1 113 482	A1	KOINUMA et al.	07-04-2001	

OTHER DOCUMENTS - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T
		RIJNDERS et al., "In situ monitoring during pulsed laser deposition of complex oxides using reflection high energy electron diffraction under high oxygen pressure," <i>Appl. Phys. Lett.</i> , Vol. 70, No. 14, pps. 1888-1890 (April 7, 1997).	

EXAMINER	DATE CONSIDERED
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*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.